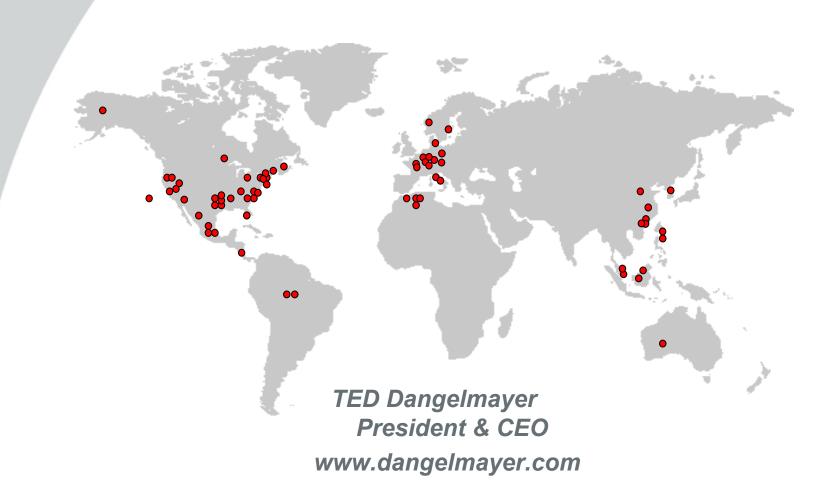


### Perfect ESD Storm!

#### CDM & Class 0 Converge in Backend

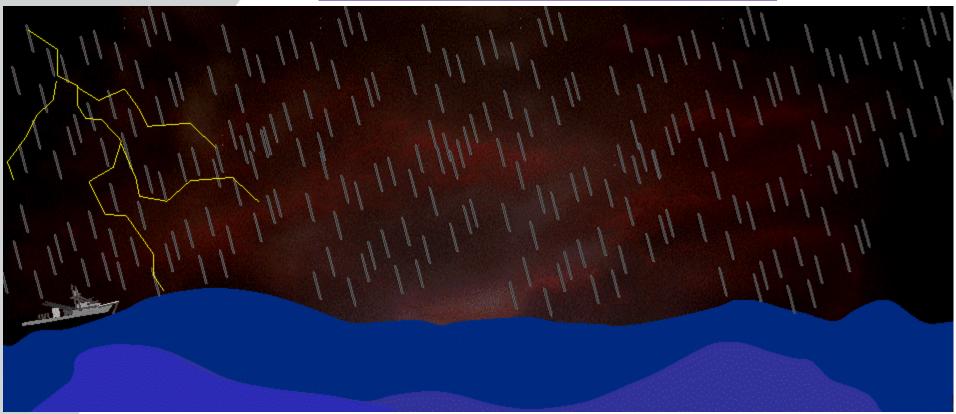


## **Outline**

- Introduction
- CDM Overview
- Lessons from the recent past
- Industry Class 0 Trend
  - It is Real This Time!
- Backend CDM Issues
- CDM & Class 0 Countermeasures
- Conclusions

#### CDM + Class 0 Trend =

#### "The Perfect ESD Storm"!

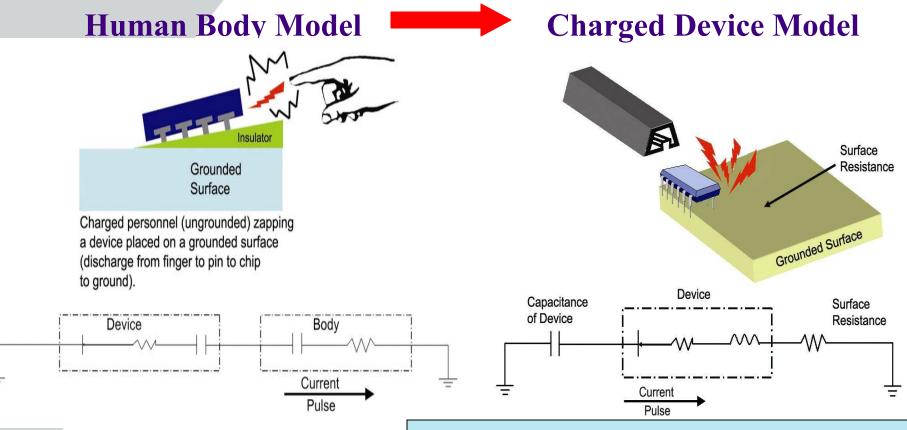


<u>Class 0</u> – Rapidly Growing Trend <u>CDM</u> Technology not Understood by Most Co's <u>CDM</u> = 95% of ESD Failures

## **CDM Overview**

#### Emergence of CDM ESD

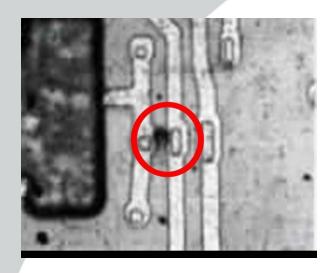
(90% to 95% of ESD Failures Today)

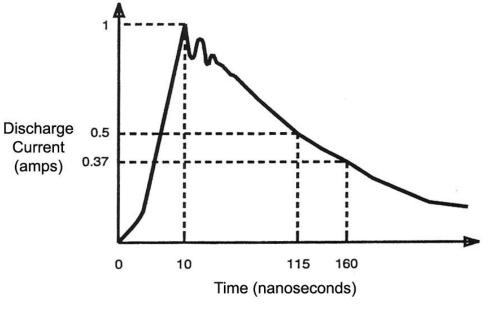


CDM Video
Tweezer Video

CDM and related metal-metal discharge events cause 95% of current ESD problems. This will continue to be the underlying driver for ESD control.

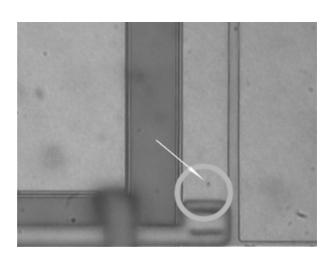
## **HBM**

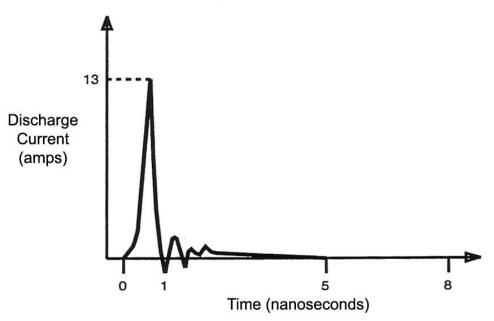




A. HBM ESD pulses

## **CDM**

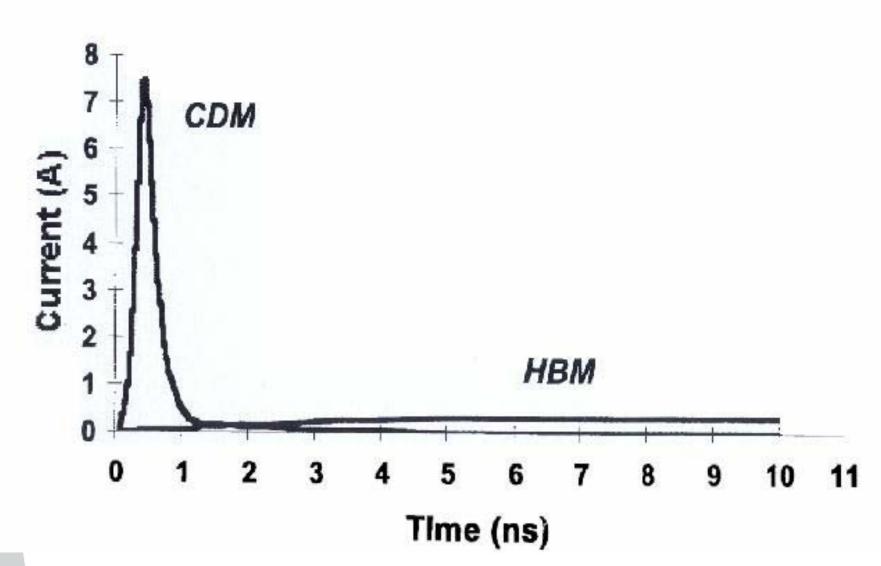




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B. CDM ESD pulses

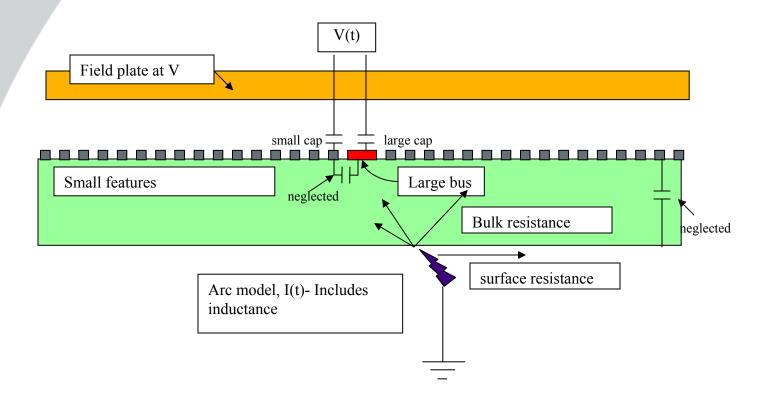
## **HBM** and **CDM** Waveforms (500v)



# Lessons from the Recent Past

### Wafer ESD Model Schematic

Wafers Will Experience ESD Damage with Technology Trend!

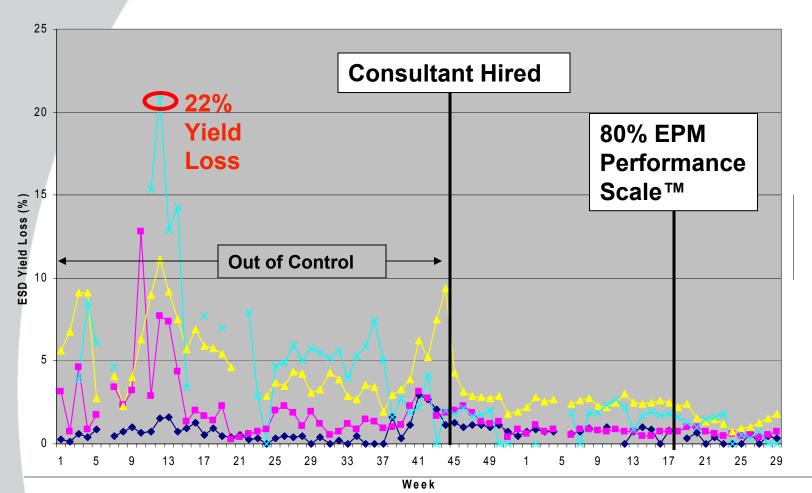


## Wafer Saw Example

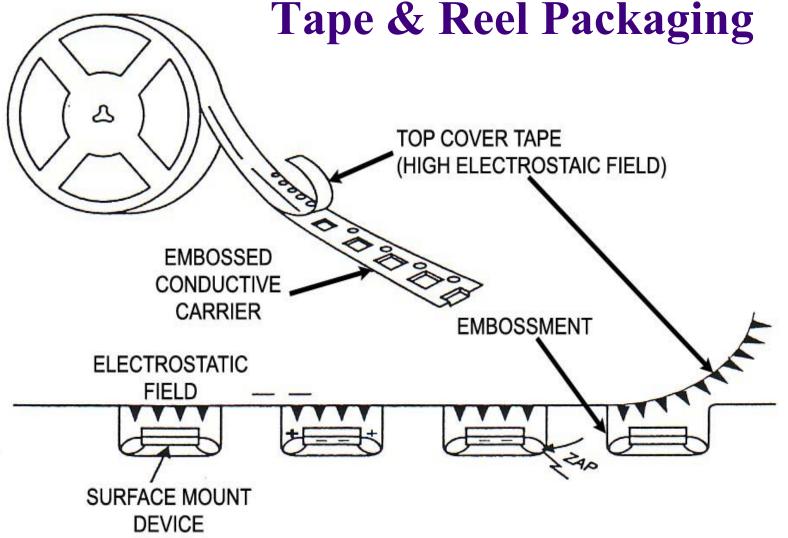
- CDM Threshold 35 Volts
- 92.2% Defective at Wafer Saw
- Failure Analysis
  - CDM Damage

## Class 0 Case Study Corresponding Yield Improvements

#### Overall ESD Yield Loss Improvements



## Class 0 CDM Failure Induced by Tape & Reel Packaging

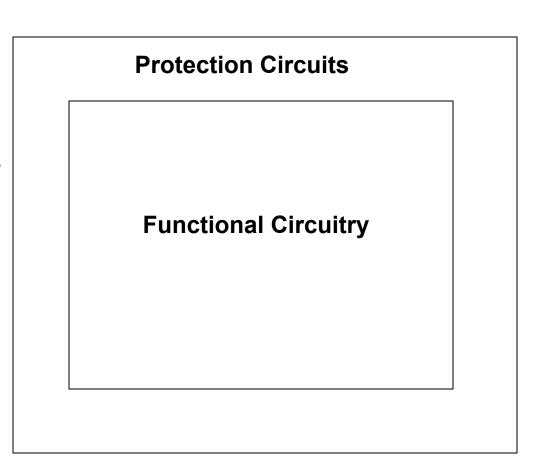


## Industry Trends It is real this time!

#### **Typical IC With Protection Circuitry**

## **Protection Circuits Constrained or Omitted By:**

- Technology Node Feature Sizes
- Circuit Functionality
- •I/O Density
- •Speed



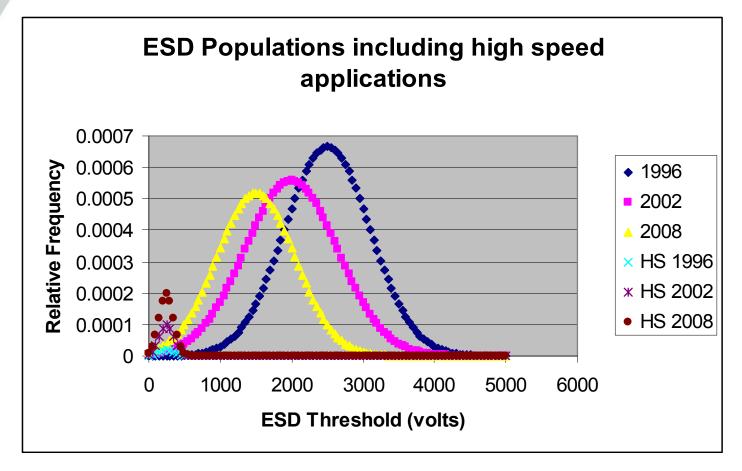
### **2003 ITRS**

A recent SEMATECH benchmarking study of integrated circuit suppliers indicated that ESD will be one of the top three reliability concerns within the next 5 years and already is with certain products!

Year	2000	2002	2003	2004	2005	2006	2007	2008	2009	2012	2015	2018
Technology Node	180nm	130nm	100nm	90 nm	80nm	70nm	65nm	55 nm	50nm	32nm	25nm	18nm
Maximum allowable electrostatic field on facility surfaces	200 V/cm	150 V/cm	125 V/cm	100 V/cm	90 V/cm	80 V/cm	70 V/cm	60 V/cm	50 V/cm	35 V/cm	25 V/cm	18 V/cm
Maximum allowable static charge on devices	2.5-10 nC (250-1000 V)		1.5 nC (150 V)	1 nC (100 V)	0.8 nC (80 V)	0.65 nC (65 V)	0.5 nC (50 V)	0.35 nC (35 V)	The second second	0.125 nC (12.5 V)	0.10 nC (10 V)	0.08 nC (8 V)
Maximum allowable electrostatic field on wafer and photomask surfaces	200 V/cm	150 V/cm	125 V/cm	100 V/cm	90 V/cm	80 V/cm	70 V/cm	60 V/cm	50 V/cm	35 V/cm	25 V/cm	18 V/cm

## ESD Threshold Populations including high speed applications

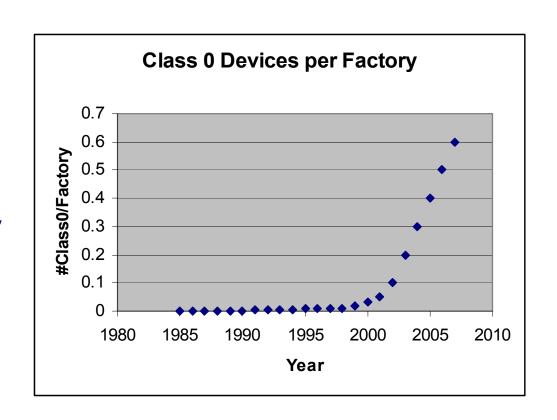
Distribution becoming bimodal



#### **Class 0 Devices per Factory**

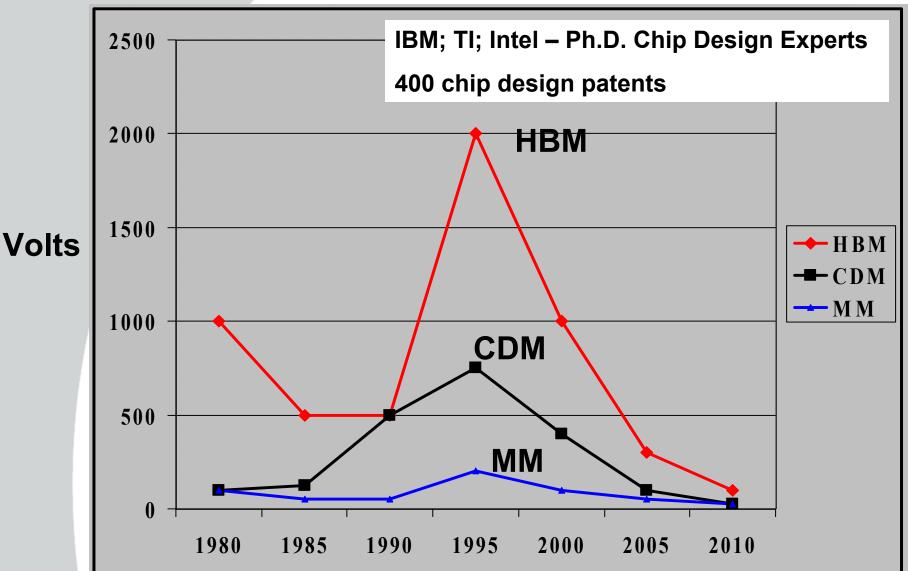
#### Class 0:

Virtually all Factories by 2010



#### ESDA Technology Roadmap

#### (IC Chip Design Experts: "With Our Best Effort")

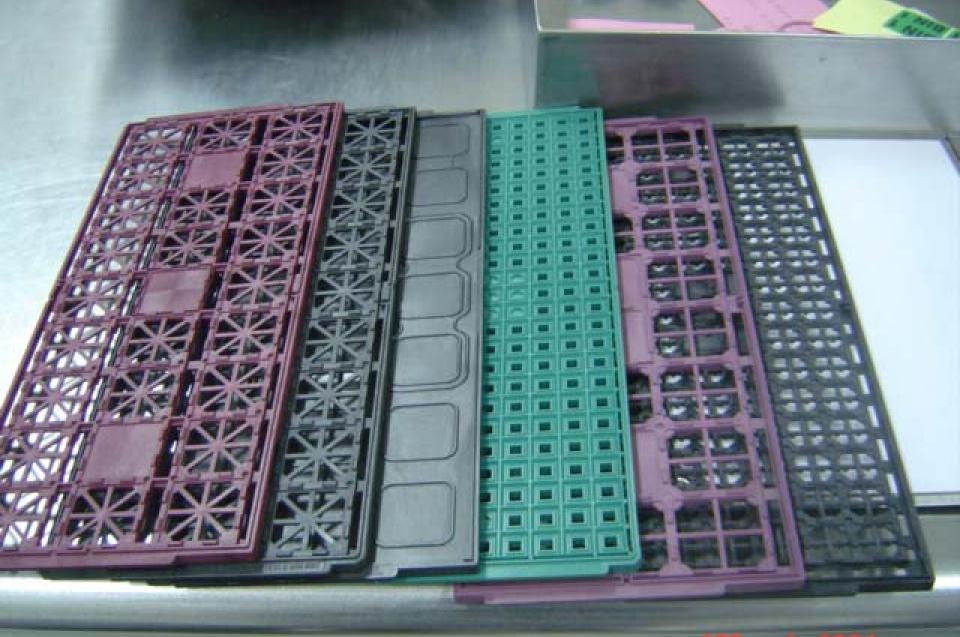


### **Sources of Trend Confirmation**

- ESD Association Roadmap
- SEMETECH ITRI Roadmap
- DA Customer Reports / Literature Analysis
- ESD Stress Test Labs
- Stress Test Equipment Manufacturers
- IC Mfg/Design: Intel; TI; IBM; AMD etc.
  - Lowering 2000 volts HBM to 1000 volts
- FA Labs
- Subcontractors Foxconn; Jabil; Solectron etc.
- OEM's Cisco, Nokia, etc.

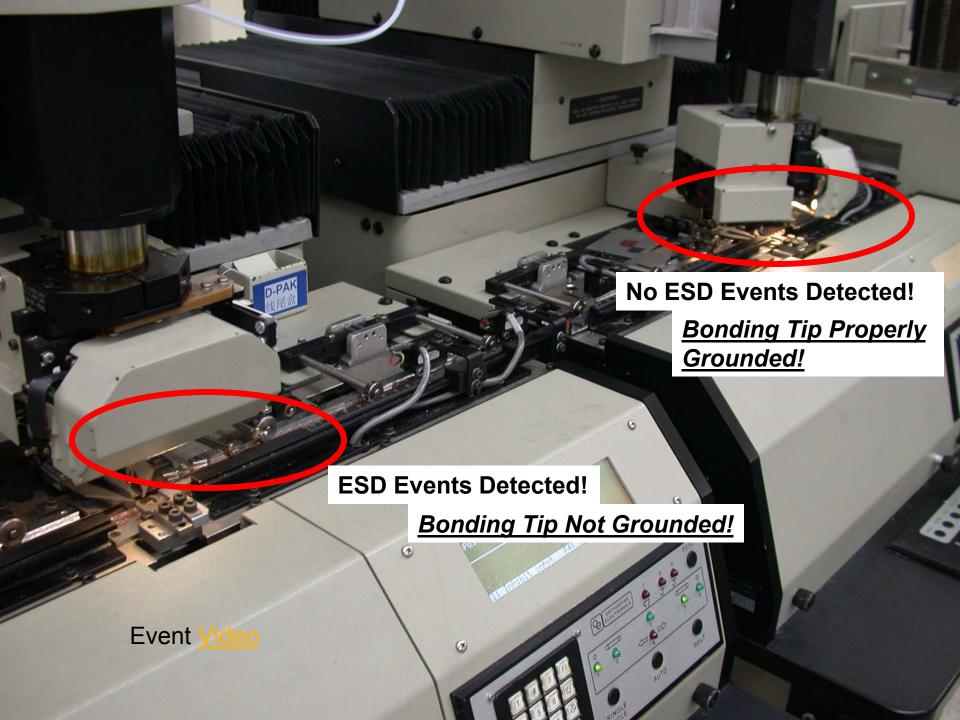


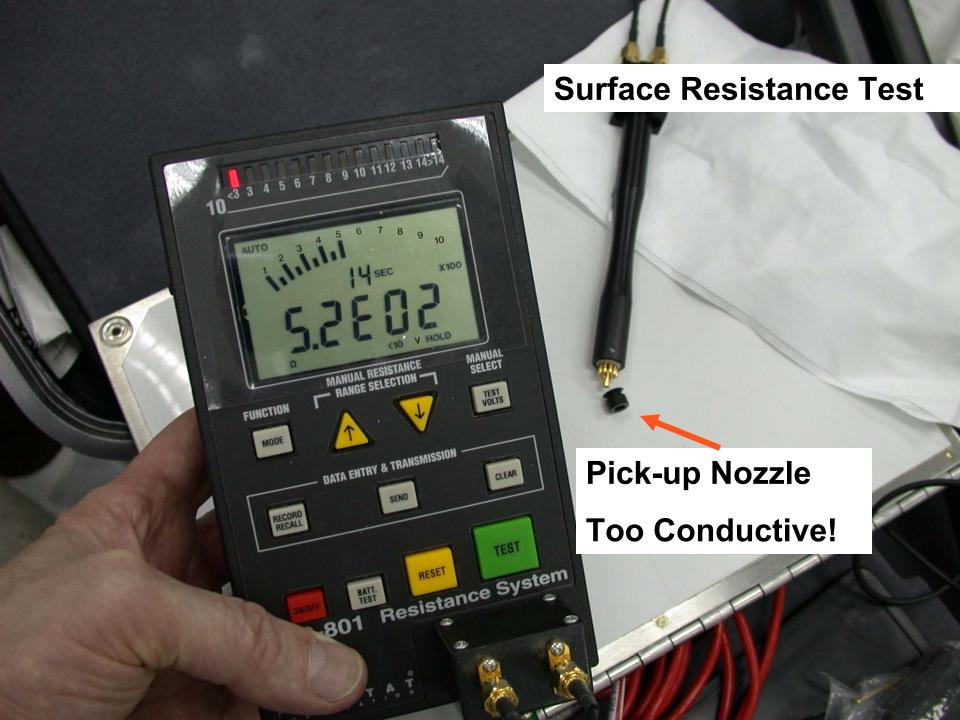
### Backend CDM Issues











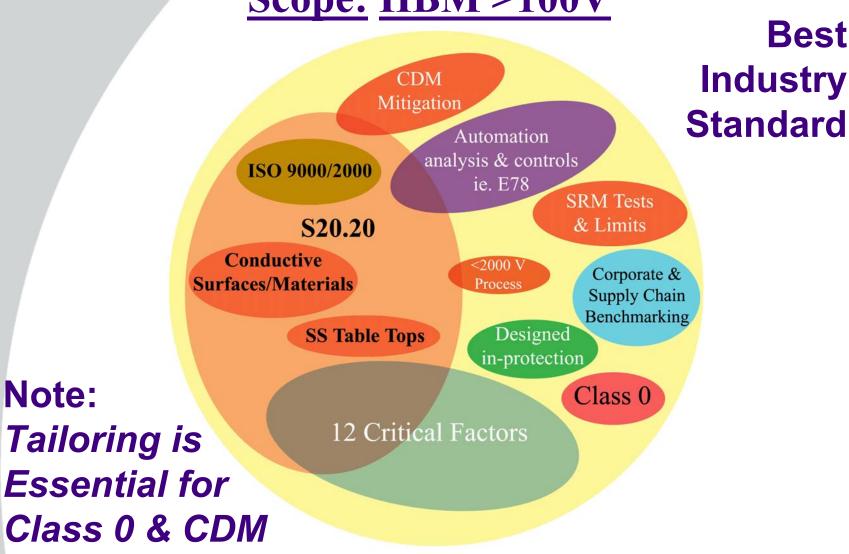






## CDM & Class 0 Countermeasures

**ESDA S20.20** Scope: HBM >100V



Note:

**Best** 



## MR Head Lessons Learned

- Conventional ESD Methods Did Not Work!
  - Below 100 Volts
  - Ionization Too Slow
  - Incomplete Coverage with Ionization
- Expect a Paradigm Shift @ 100 volts
  - Assume Device Still Charged!
- New Control Methods
  - Eliminate Metal-to-Metal Contact
  - Substitute "Soft Landings" with Dissipative Materials



### **Conclusions**

#### CDM + Class 0 Trend = Perfect ESD Storm!

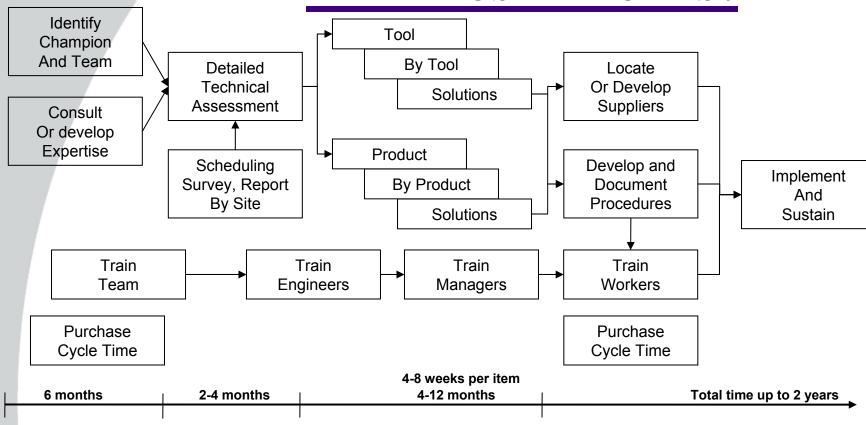
#### **Trend Drivers:**

- Class 0:
  - Virtually All Factories By 2010!
  - It Takes Two Year To Prepare
- Trends Driven By
  - Exploding Consumer Markets
  - High Volume Production
- Designed-in Protection Circuits Limited
  - By Speed Of Application And I/O Density

#### <u>Impact On Control Procedures:</u>

- Standard Control Procedures
  - Insufficient But Necessary
- Paradigm Shift In Control Techniques
  - Occurs At 100 Volts
  - Must Assume Product Is Still Charged
  - Ionization Often Not Sufficient
- Metal-to-metal Contact Must Be Eliminated
- EMI/ESD Event Testing Is Essential

# Class 0 - Are You Ready? It Takes 2 Years!



**Initiate -> Assess -> Design -> Develop -> Implement** 

HS1203